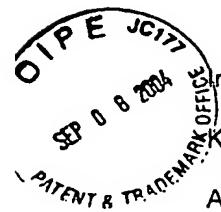


IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



In Re the Application of

KOLESNYCENKO et al.

Application No.: 10/823,777

Filed: April 14, 2004

Group Art Unit: 1756

Examiner: Unassigned

Confirmation No.: 4703

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

September 8, 2004

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents

P. O. Box 1450

Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

| Examiner's Initials | First Inventor | Application No. | Filing Date | Enclosed |
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| KG | DE SMIT (081468-0309173) | 10/820,227 | 04/08/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | DE SMIT (081468-0309978) | 10/860,662 | 06/04/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | DUINEVELD et al. (081468-0308101) | 10/773,461 | 02/09/2004 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
| | FLAGELLO et al. (081468-0302644) | 10/698,012 | 10/31/2003 | <input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card |
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*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

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| | | | | 309196 |

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Date: September 8, 2004

Page 1 of 4

Applicant: KOLESNYCHENKO et al.

Appln. No. 10/823,777

Filing Date: April 14, 2004

Examiner: *Uakrowa*

Group Art Unit: 1756 2851

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Date Considered: 02/13/2007

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| | | | | | | | 309196 P-1851.000-US | | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | | | | Applicant: KOLESNYCHENKO et al. | | | | |
| | | | | | Appln. No. 10/823,777 | | | | |
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| Date: September 8, 2004 | | Page 2 of 4 | Examiner: Unknown | | Group Art Unit: 4750 2851 | | | | |
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PTO/SB/08a (08-03)

Approved for use through 07/31/2006. OMB 0651-0031
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| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | | | Complete if Known | |
| | | | | Application Number | 10/823,777 |
| | | | | Filing Date | 04/14/2004 |
| | | | | First Named Inventor | ALEKSEY KOLESNYCHENKO |
| | | | | Art Unit | 1756 2851 |
| | | | | Examiner Name | Unassigned Gutierrez, K. |
| | | | | Attorney Docket Number | 081468-0309196 |
| (Use as many sheets as necessary) | | | | | |
| Sheet | 1 | of | 1 | | |

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| Examiner Signature | /Kevin Gutierrez/ | Date Considered | 02/13/2007 |
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